

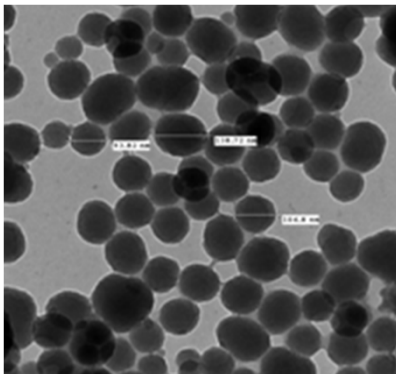


# **ACESOL® WP100H** (Wafer Stock Polishing Slurry)

## **DESCRIPTION**

Acesol® slurries offer a complete solution for your polishing requirements based on the latest colloidal silica technology showing exceptional stability and high manufacturing reproducibility

### **TEM Image**



Precisely Controlled  
ACESOL® Particles.

## **KEY FEATURES**

- Non-agglomerating slurries with tight Particle distributions
- Enables high removal rates
- Low solid contents, excellent uniformity, no defect
- Products development for customized applications
- Individual, non-setting spherical particles

## **SPECIFICATION**

<b>Abrasive</b>	<b>Colloidal Silica</b>
<b>Mean Particle</b>	<b>70 -120 nm</b>
<b>Specific Gravity (20℃) g/cc</b>	<b>1.120</b>
<b>Solid Content (wt%)</b>	<b>20</b>
<b>Viscosity (25℃) cps</b>	<b>&lt;5</b>
<b>pH (20℃)</b>	<b>11.15</b>
<b>Shelf life</b>	<b>1 Year</b>

### **Metal impurity (Unit:ppm)**

<b>Metal</b>	<b>Result</b>	<b>Spec</b>
Na	700	<1000
Al	85	<100
Fe	15	<30
Cr	ND	<0.5
Cu	23 (ppb)	<40(ppb)
Ni	27 (ppb)	<40(ppb)